

1. Please indicate whether a chamber is desired with this system and any other information you feel is important.

**The chamber desired with this system is considered to be the baseplate shroud described in Specification No. 8. It should be 400 millimeters in diameter.**

2. Would a multi-pocket electron beam gun be acceptable as the source? This source would be a 7cc capacity.

**No. An electron beam gun does not provide the required low temperature organic vapor sources.**

3. What is the size of the anticipated substrate and how many will be coated during one process run?

**Substrates will be up to 6 inches in diameter, one wafer per process run.**

4. As no external air supply is available to operate the vacuum valves, is it possible for us to supply an integral air system to perform the pneumatics?

**Yes, as long as the external air supply has some sort of battery backup so that the solenoids would actuate (and seal the vacuum system) if power was lost.**